

REMARKS

The specification and abstract have been amended to conform with proper grammar and idiomatic language. No new matter has been added.

Claims 1 and 3-5 have been rejected under 35 USC 102(e) as anticipated by Hong. The rejection is respectfully traversed.

Hong discloses, with reference to Figures 1-4, a formation and filling of a trench in two steps up to a level of the top side of the mask. The first insulating material 21 is a spin on glass (col. 4, ln. 8). This layer does not selectively grow in the trench (as required by the claimed invention), but rather is applied over the whole structure as seen in Figure 2, which shows a small fraction of the spin on glass as well on the top side of the mask.

In the claimed invention, on the other hand, only the trench is filled. This unique feature ensures the upper area formed by the mask will not be filled in the first step. Hence, no closing of the top area occurs, and formation of internal cavities in the trench are avoided. Additionally, in Hong, by applying the silicon nitride layer 17 on the mask and in the trench before spinning on the glass, surfaces of the mask and the trench are made chemically identical, which renders a selective growth impossible.

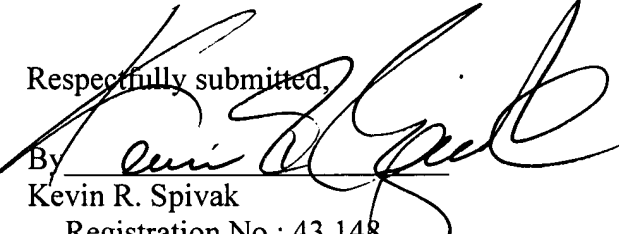
Claim 2 has been rejected under 35 USC 103(a) as unpatentable over Hong in view of Curtis. The rejection is respectfully traversed for the same reasons presented in the arguments above, and for the following reason. Curtis fails to disclose a layer selectively growing in the trench, as required by the claimed invention.

In view of the above, each of the presently pending claims in this application is believed to be in immediate condition for allowance. Accordingly, the Examiner is respectfully requested to withdraw the outstanding rejection of the claims and to pass this application to issue. If it is determined that a telephone conference would expedite the prosecution of this application, the Examiner is invited to telephone the undersigned at the number given below.

In the event the U.S. Patent and Trademark office determines that an extension and/or other relief is required, applicant petitions for any required relief including extensions of time and authorizes the Commissioner to charge the cost of such petitions and/or other fees due in connection with the filing of this document to Deposit Account No. 03-1952 referencing docket no. 543822005000. However, the Commissioner is not authorized to charge the cost of the issue fee to the Deposit Account.

Dated: November 22, 2005

Respectfully submitted,

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